	Тур е	L #	Hit s	Search Text	DBs	Time Stamp	Comme nts
1	BRS	L1	129 280	(polymer\$3 or residue or stringers) same (NH3 or ammonia or hydrogen or H2)	USP AT	2002/0 3/15 13:07	
2					USP AT	3/15	
3	BRS	L3	76	1 and 2	AT	2002/0 3/15 13:35	
4	BRS	L 7	123 612	(photoresist or resist) and (opening or via)	JPO	2002/0 3/15 14:54	
5	BRS	L8	452	1 and 7	USP AT; EPO; JPO; IBM TD B	2002/0 3/15 13:38	
6	BRS	S L9	98	8 and chuck and chamber	USP AT; EPC; JPC; IBM TI	2002/0 3/15 13:42)
7	BR	s D	1 16	4 8 and (etch\$4 or getter\$4)	USI AT, EP(; JP(; IBI _T; B	2002/ 2002/ 3/15 13:43	

	Тур	L #	Hit s	Search Text	DBs	Time Stamp	Comme nts
3	BRS	L1 1	983	·	JPO; ; IBM TD B	2002/0 3/15 13:44	
9	BRS	L1 2	542	11 and semiconductor	JPO	2002/0 3/15 13:45	
10	BRS	L1 6	602	hydrocarbons same polymer\$3 same plasma	; IBM _TD B	2002/0 3/15 15:08	
11	IS& R	L1	118	((438/706) or (438/710) or (438/712) or (438/714)).CCLS.	USF AT	2002/0 3/15 15:09)
12	BRS	L1	13	16 and 17	USF AT; EPC; JPC; IBN _TI	2002/0 3/15 15:18	
13	BRS	L2 5 1	2 20	polymer same clean\$4 same ("CO.sub.2" or "carbon dioxide")	US AT	15:26	
14	BRS	S L	2 1	6200412.pn.	US: AT		